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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-1674		PRIORITY SERIAL NO. 09/752,685	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Shane J. Trapp		09/920978	
					PRIORITY FILING DATE January 3, 2001		PRIORITY GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
DSN	AA	5,989,987	11/1999	Kuo	438/	592		
DSN	AB	09/752,685		Trapp			01/03/01 PTO	
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
	AL							
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AM							
	AN							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AO							
	AP							
	AQ							
	AR							
EXAMINER <u>DSN</u>				DATE CONSIDERED 2/14/02				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1674	SERIAL NO. 09/920,978		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shane J. Trapp			
				FILING DATE August 1, 2001	GROUP 2813		
U.S. PATENT DOCUMENTS							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
DB	AA	3,990,927	11/09/76	Montier	156	8	RECEIVED OCT - 7 2002 TECHNOLOGY CENTER 2800
DB	AB	4,474,975	10/02/84	Clemons et al.	556	410	
DB	AC	5,156,881	10/20/92	Okano et al.	427	572	
DB	AD	5,182,221	01/26/93	Sato	437	67	
DB	AE	5,410,176	04/25/95	Liou et al.	257	50	
DB	AF	5,470,798	11/28/95	Ouellet	437	231	
DB	AG	5,719,085	02/17/98	Moon et al.	438	424	
DB	AH	5,741,740	04/21/98	Jang et al.	438	435	
DB	AI	5,776,557	07/07/98	Okano et al.	427	579	
DB	AJ	5,786,039	07/28/98	Brouquet	427	578	
DB	AK	5,801,083	09/01/98	Yu et al.	438	424	
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes No	
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
DB	AN	Beekmann et al., Sub-micron Gap Fill and In-Situ Planarisation Using Flowfill™ Technology,					
		Electrotech, Presented at ULSI Conference, Portland, Oregon (October 1995). ✓					
DB	AO	Horie et al., Kinetics and Mechanism of the Reactions of O ² P With SiH ₄ , CH ₃ SiH ₃ ,					
		(CH ₃) ₂ SiH ₂ , and (CH ₃) ₃ SiH, 95 J. PHYS. CHEM. No. 95, pp. 4393-4400 (1991). ✓					
DB	AP	Joshi et al., Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for					
		Entirely Dry Mid-Deep UV Photolithography, 1925 SPIE 709-720 (1993). ✓					
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A. D. Sn			11/2/02				
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FILING DATE August 1, 2001				GROUP 2813	

U.S. PATENT DOCUMENTS							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
	AA	5,863,827	Joyner	438	425	RECEIVED OCT - 7 2002 TECHNOLOGY CENTER 2800	
	AB	5,883,006	Iba	438	712		
DB	AC	5,888,880	Gardner et al.	438	424		
DB	AD	5,895,253	Akram	438	424		
DB	AE	5,904,540	Sheng et al.	438	427		
DB	AF	5,930,645	Lyons et al.	438	424		
DB	AG	5,943,585	May et al.	438	400		
DB	AH	5,950,094	Lin et al.	438	409		
DB	AI	5,960,299	Yew et al.	438	424		
DB	AJ	5,972,773	Liu et al.	438	424		
DB	AK	5,998,280	Bergemont et al.	438	425		

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Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
DB	AN	Kiermasz et al., <i>Planarization for Sub-Micron Devices Utilising a New Chemistry</i> , Electrotech, Presented at DUMIC Conference, California (February 1995).
DB	AO	Matsuura et al., <i>A Highly Reliable Self-planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects</i> , IEEE 785-788 (1997).
DB	AP	Matsuura et al., <i>Novel Self-planarizing CVD Oxide for Interlayer Dielectric Applications</i> , IEEE 117-120 (1994).

EXAMINER 	DATE CONSIDERED 1/12/03
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 U.S. DEPARTMENT OF COMMERCE
 PATENT AND TRADEMARK OFFICE

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 (Use several sheets if necessary)

ATTY. DOCKET NO.
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SERIAL NO.
 09/920,978

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 August 1, 2001

GROUP
 2813

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DB	AA	6,030,881	02/29/00	Papasoulotis et al.	438	424	
DB	AB	6,051,477	04/18/00	Nam	438	404	
DB	AC	6,156,674	12/05/00	Li et al.	438	780	
DB	AD	6,300,219 B1	10/09/01	Doan et al.	438	424	
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

DB	AN	McClatchie et al., Low Dielectric Constant Flowfil [®] Technology for IMD Applications,
		7 pages (pre-August 1993).
DB	AO	Withnall et al., Matrix Reactions of Methylsilanes and Oxygen Atoms, 92 J. PHYS. CHEM.,
		No. 3, pp. 594-602 (1988)
	AP	

EXAMINER RD DATE CONSIDERED 11/2/03

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